Available online at www.sciencedirect.com
SCIENCE DIRECT®

Polymer 44 (2003) 7779

polymer

www.elsevier.com/locate/polymer

Erratum

Erratum to: 'Enabling nanotechnology with self assembled block copolymer patterns' [Polymer 44 (23) 6725–6760]☆

Cheolmin Park[a], Jongseung Yoon[b], Edwin L. Thomas[b,c,*]

[a]*Department of Metallurgical System Engineering, Yonsei University, Seoul 120-749, South Korea*
[b]*Department of Materials Science and Engineering, Massachusetts Institute of Technology, Room 13-5094, 77 Massachusetts Avenue, Cambridge, MA 02139, USA*
[c]*Institute for Soldier Nanotechnologies, Massachusetts Institute of Technology, Cambridge, MA 02139, USA*

The publishers regret that when this article was published there was an error in the Acknowledgements section. The text should be as follows:

C. Park thanks the Ministry of Science and Technology, the Republic of Korea, for financial support through the R & D Program for NT-IT Fusion Strategy of Advanced Technologies. J. Yoon thanks the National Science Foundation for financial support under Grant No. 0103297 (NSF-NIRT). This research was supported in part by the US Army through the Institute for Soldier Nanotechnologies, under Contract DAAD-19-02-D-0002 with the US Army Research Office. The content does not necessarily reflect the position of the Government, and no official endorsement should be inferred.

☆ doi of original article 10.1016/J.POLYMER.2003.08.011

* Corresponding author. Address: Department of Materials Science and Engineering, Massachusetts Institute of Technology, Room 13-5094, 77 Massachusetts Avenue, Cambridge, MA 02139, USA. Tel.: +1-617-253-5931; fax: +1-617-253-5859.

E-mail address: elt@mit.edu (E.L. Thomas).

0032-3861/$ - see front matter
doi:10.1016/j.polymer.2003.09.052